

# Achim von Keudell

## List of Publications by Year in descending order

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161  
papers

5,520  
citations

71004

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116156

66  
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163  
all docs

163  
docs citations

163  
times ranked

3524  
citing authors

#	ARTICLE	IF	CITATIONS
1	Ion-induced secondary electron emission of oxidized nickel and copper studied in beam experiments. Plasma Sources Science and Technology, 2022, 31, 025017.	1.3	6
2	Propagation of nanosecond plasmas in liquids – Streamer velocities and streamer lengths. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2022, 40, 043003.	0.9	2
3	Foundations of physical vapor deposition with plasma assistance. Plasma Sources Science and Technology, 2022, 31, 083001.	1.3	27
4	Dedicated setup to isolate plasma catalysis mechanisms. Journal Physics D: Applied Physics, 2021, 54, 134005.	1.3	5
5	Oxygen Removal from a Hydrocarbon Containing Gas Stream by Plasma Catalysis. Plasma Chemistry and Plasma Processing, 2021, 41, 619-642.	1.1	4
6	Ignition and propagation of nanosecond pulsed plasmas in distilled water – Negative vs positive polarity applied to a pin electrode. Journal of Applied Physics, 2021, 129, .	1.1	5
7	Link between plasma properties with morphological, structural and mechanical properties of thin Ti films deposited by high power impulse magnetron sputtering. Surface and Coatings Technology, 2021, 418, 127235.	2.2	14
8	Excitation and dissociation of CO <sub>2</sub> heavily diluted in noble gas atmospheric pressure plasma. Journal Physics D: Applied Physics, 2020, 53, 125205.	1.3	29
9	Pattern Formation in High Power Impulse Magnetron Sputtering (HiPIMS) Plasmas. Plasma Chemistry and Plasma Processing, 2020, 40, 643-660.	1.1	13
10	SiO <sub>2</sub> microstructure evolution during plasma deposition analyzed via ellipsometric porosimetry. Plasma Processes and Polymers, 2020, 17, 2000036.	1.6	0
11	Chemistry in nanosecond plasmas in water. Plasma Processes and Polymers, 2020, 17, 1900192.	1.6	11
12	Study of the transition from self-organised to homogeneous plasma distribution in chromium HiPIMS discharge. Journal Physics D: Applied Physics, 2020, 53, 155201.	1.3	13
13	Electron density, temperature and the potential structure of spokes in HiPIMS. Plasma Sources Science and Technology, 2020, 29, 025006.	1.3	25
14	Nanosecond pulsed discharges in distilled water: I. Continuum radiation and plasma ignition. Plasma Sources Science and Technology, 2020, 29, 095008.	1.3	18
15	Nanosecond pulsed discharges in distilled water-Part II: line emission and plasma propagation. Plasma Sources Science and Technology, 2020, 29, 085021.	1.3	11
16	Velocity distribution of metal ions in the target region of HiPIMS: the role of Coulomb collisions. Plasma Sources Science and Technology, 2020, 29, 125003.	1.3	8
17	Nanosecond plasmas in water: ignition, cavitation and plasma parameters. Plasma Sources Science and Technology, 2019, 28, 085003.	1.3	26
18	SiO <sub>2</sub> microstructure evolution during plasma deposition analyzed via ellipsometric porosimetry. Plasma Processes and Polymers, 2019, 16, 1900015.	1.6	1

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19	Validation of etching model of polypropylene layers exposed to argon plasmas. <i>Plasma Processes and Polymers</i> , 2019, 16, 1900019.	1.6	11
20	Influence of spokes on the ionized metal flux fraction in chromium high power impulse magnetron sputtering. <i>Journal Physics D: Applied Physics</i> , 2018, 51, 115201.	1.3	23
21	Decoupling of ion and photon activation mechanisms in polymer surfaces exposed to low temperature plasmas. <i>Plasma Processes and Polymers</i> , 2018, 15, 1700230.	1.6	5
22	Velocity distribution of titanium neutrals in the target region of high power impulse magnetron sputtering discharges. <i>Plasma Sources Science and Technology</i> , 2018, 27, 105012.	1.3	19
23	Connection between target poisoning and current waveforms in reactive high-power impulse magnetron sputtering of chromium. <i>Plasma Sources Science and Technology</i> , 2018, 27, 084004.	1.3	8
24	Non-equilibrium excitation of CO <sub>2</sub> in an atmospheric pressure helium plasma jet. <i>Journal Physics D: Applied Physics</i> , 2018, 51, 345202.	1.3	17
25	Spokes in high power impulse magnetron sputtering plasmas. <i>Journal Physics D: Applied Physics</i> , 2018, 51, 453001.	1.3	42
26	Fast charge exchange ions in high power impulse magnetron sputtering of titanium as probes for the electrical potential. <i>Plasma Sources Science and Technology</i> , 2017, 26, 035007.	1.3	14
27	Influence of nitrogen admixture to argon on the ion energy distribution in reactive high power pulsed magnetron sputtering of chromium. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 135203.	1.3	17
28	Species transport on the target during high power impulse magnetron sputtering. <i>Applied Physics Letters</i> , 2017, 110, 081603.	1.5	8
29	Electric potential screening on metal targets submitted to reactive sputtering. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017, 35, .	0.9	7
30	Review Article: Unraveling synergistic effects in plasma-surface processes by means of beam experiments. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017, 35, 050801.	0.9	16
31	Correlative plasma-surface model for metastable Cr-Al-N: Frenkel pair formation and influence of the stress state on the elastic properties. <i>Journal of Applied Physics</i> , 2017, 121, .	1.1	27
32	Absolutely calibrated mass spectrometry measurement of reactive and stable plasma chemistry products in the effluent of a He/H <sub>2</sub> O atmospheric plasma. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 335204.	1.3	23
33	Composite targets in HiPIMS plasmas: Correlation of in-vacuum XPS characterization and optical plasma diagnostics. <i>Journal of Applied Physics</i> , 2017, 121, 171912.	1.1	10
34	Investigation of plasma spokes in reactive high power impulse magnetron sputtering discharge. <i>Journal of Applied Physics</i> , 2017, 121, .	1.1	16
35	Foundations of low-temperature plasma physics – an introduction. <i>Plasma Sources Science and Technology</i> , 2017, 26, 113001.	1.3	72
36	Probing the electron density in HiPIMS plasmas by target inserts. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 505204.	1.3	26

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37	Fundamental study of an industrial reactive HPPMS (Cr,Al)N process. Journal of Applied Physics, 2017, 122, .	1.1	17
38	Control of High Power Pulsed Magnetron Discharge by Monitoring the Current Voltage Characteristics. Contributions To Plasma Physics, 2016, 56, 918-926.	0.5	9
39	Revising secondary electron yields of ion-sputtered metal oxides. Journal Physics D: Applied Physics, 2016, 49, 16LT01.	1.3	30
40	Sampling of ions at atmospheric pressure: ion transmission and ion energy studied by simulation and experiment. European Physical Journal D, 2016, 70, 1.	0.6	7
41	Methods of gas purification and effect on the ion composition in an RF atmospheric pressure plasma jet investigated by mass spectrometry. EPJ Techniques and Instrumentation, 2016, 3, .	0.5	7
42	Gepulste Hochleistungs-Magnetron-Plasmen (HPPMS). Vakuum in Forschung Und Praxis, 2016, 28, 24-27.	0.0	0
43	Spoke rotation reversal in magnetron discharges of aluminium, chromium and titanium. Plasma Sources Science and Technology, 2016, 25, 035001.	1.3	51
44	Note: Ion-induced secondary electron emission from oxidized metal surfaces measured in a particle beam reactor. Review of Scientific Instruments, 2015, 86, 106102.	0.6	31
45	Elementary surface processes during reactive magnetron sputtering of chromium. Journal of Applied Physics, 2015, 118, 133301.	1.1	7
46	Exploring the Structure of the Modified Top Layer of Polypropylene During Plasma Treatment. Plasma Processes and Polymers, 2015, 12, 564-573.	1.6	15
47	Fundamentals and Applications of Reflection FTIR Spectroscopy for the Analysis of Plasma Processes at Materials Interfaces. Plasma Processes and Polymers, 2015, 12, 926-940.	1.6	16
48	Mass spectrometry of atmospheric pressure plasmas. Plasma Sources Science and Technology, 2015, 24, 044008.	1.3	54
49	High power impulse sputtering of chromium: correlation between the energy distribution of chromium ions and spoke formation. Journal Physics D: Applied Physics, 2015, 48, 295202.	1.3	22
50	Spoke transitions in HiPIMS discharges. Plasma Sources Science and Technology, 2015, 24, 045005.	1.3	42
51	The effect of surface reactions of O, O <sub>3</sub> and N on film properties during the growth of silica-like films. Journal Physics D: Applied Physics, 2014, 47, 224005.	1.3	2
52	Origin of the energetic ions at the substrate generated during high power pulsed magnetron sputtering of titanium. Journal Physics D: Applied Physics, 2014, 47, 224002.	1.3	86
53	Combined In Situ XPS and UHV-Chemical Force Microscopy (CFM) Studies of the Plasma Induced Surface Oxidation of Polypropylene. Plasma Processes and Polymers, 2014, 11, 256-262.	1.6	10
54	Fast Time Resolved Techniques as Key to the Understanding of Energy and Particle Transport in HPPMS-Plasmas. IEEE Transactions on Plasma Science, 2014, 42, 2812-2813.	0.6	4

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55	Adsorption and reactivity of nitrogen atoms on silica surface under plasma exposure. Journal Physics D: Applied Physics, 2014, 47, 475204.	1.3	19
56	Various Shapes of Plasma Spokes Observed in HiPIMS. IEEE Transactions on Plasma Science, 2014, 42, 2810-2811.	0.6	3
57	Target implantation and redeposition processes during high-power impulse magnetron sputtering of aluminum. Journal Physics D: Applied Physics, 2013, 46, 084009.	1.3	4
58	Time-resolved measurement of film growth during high-power pulsed magnetron sputtering (HIPIMS) of titanium. Journal Physics D: Applied Physics, 2013, 46, 155204.	1.3	10
59	Time-resolved measurement of film growth during reactive high power pulsed magnetron sputtering (HIPIMS) of titanium nitride. Journal Physics D: Applied Physics, 2013, 46, 495201.	1.3	5
60	Dynamic of the growth flux at the substrate during high-power pulsed magnetron sputtering (HiPIMS) of titanium. Journal Physics D: Applied Physics, 2013, 46, 485204.	1.3	32
61	Particle beam experiments for the analysis of reactive sputtering processes in metals and polymer surfaces. Review of Scientific Instruments, 2013, 84, 103303.	0.6	20
62	Bimodal substrate biasing to control $\text{Al}_2\text{O}_3$ deposition during reactive magnetron sputtering. Journal of Applied Physics, 2013, 114, 113301.	1.1	14
63	Chemical and Physical Sputtering of Polyethylene Terephthalate (PET). Plasma Processes and Polymers, 2013, 10, 225-234.	1.6	17
64	Formation of crystalline $\text{Al}_2\text{O}_3$ induced by variable substrate biasing during reactive magnetron sputtering. Journal Physics D: Applied Physics, 2013, 46, 084004.	1.3	16
65	Nonlinear evolution of surface morphology under shadowing. Physical Review E, 2013, 87, 042404.	0.8	2
66	Surface Modification of Polypropylene (PP) by Argon Ions and UV Photons. Plasma Processes and Polymers, 2013, 10, 1110-1119.	1.6	22
67	Insight into the Reaction Scheme of $\text{SiO}_2$ Film Deposition at Atmospheric Pressure. Plasma Processes and Polymers, 2013, 10, 1061-1073.	1.6	32
68	Ion-induced oxidation of aluminum during reactive magnetron sputtering. Journal of Applied Physics, 2013, 113, 143303.	1.1	10
69	Development of the sputtering yields of ArF photoresist after the onset of argon ion bombardment. Journal of Applied Physics, 2013, 113, .	1.1	3
70	Embedded argon as a tool for sampling local structure in thin plasma deposited aluminum oxide films. Journal of Applied Physics, 2012, 112, .	1.1	4
71	Unexpected O and $\text{O}_3$ production in the effluent of $\text{He/O}_2$ microplasma jets emanating into ambient air. Plasma Sources Science and Technology, 2012, 21, 034019.	1.3	82
72	Functional plasma polymers deposited in capacitively and inductively coupled plasmas. Applied Physics Letters, 2012, 100, .	1.5	15

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73	Time-resolved measurement of film growth during high-power pulsed magnetron sputtering (HPPMS) of titanium: the rotating shutter concept. Journal Physics D: Applied Physics, 2012, 45, 402001.	1.3	9
74	Quadrupole mass spectrometry of reactive plasmas. Journal Physics D: Applied Physics, 2012, 45, 403001.	1.3	90
75	The Role of Oxygen and Surface Reactions in the Deposition of Silicon Oxide like Films from HMDSO at Atmospheric Pressure. Plasma Processes and Polymers, 2012, 9, 1116-1124.	1.6	43
76	X-ray photoelectron spectroscopy on implanted argon as a tool to follow local structural changes in thin films. Thin Solid Films, 2011, 520, 1625-1630.	0.8	17
77	Surface reactions as carbon removal mechanism in deposition of silicon dioxide films at atmospheric pressure. Applied Physics Letters, 2011, 98, 111502.	1.5	24
78	Phase resolved optical emission spectroscopy of coaxial microplasma jet operated with He and Ar. European Physical Journal D, 2010, 60, 539-546.	0.6	27
79	Elimination of Biological Contaminations from Surfaces by Plasma Discharges: Chemical Sputtering. ChemPhysChem, 2010, 11, 1382-1389.	1.0	38
80	Inactivation of Bacteria and Biomolecules by Low-Pressure Plasma Discharges. Plasma Processes and Polymers, 2010, 7, 327-352.	1.6	137
81	A Physicist's Perspective on "Views on Macroscopic Kinetics of Plasma Polymerisation". Plasma Processes and Polymers, 2010, 7, 376-379.	1.6	31
82	Ion-enhanced oxidation of aluminum as a fundamental surface process during target poisoning in reactive magnetron sputtering. Journal of Applied Physics, 2010, 107, .	1.1	28
83	Calibration of a miniaturized retarding field analyzer for low-temperature plasmas: geometrical transparency and collisional effects. Journal Physics D: Applied Physics, 2010, 43, 055203.	1.3	38
84	Fundamental aspects of substrate biasing: ion velocity distributions and nonlinear effects. Journal Physics D: Applied Physics, 2010, 43, 335201.	1.3	20
85	Characterization of the effluent of a He/O <sub>2</sub> microscale atmospheric pressure plasma jet by quantitative molecular beam mass spectrometry. New Journal of Physics, 2010, 12, 013021.	1.2	173
86	Molecular beam sampling system with very high beam-to-background ratio: The rotating skimmer concept. Review of Scientific Instruments, 2009, 80, 055107.	0.6	33
87	Deposition of silicon dioxide films using an atmospheric pressure microplasma jet. Journal of Applied Physics, 2009, 105, .	1.1	68
88	The role of C <sub>2</sub> H <sub>4</sub> for the acetylene chemistry in particle forming Ar/He/C <sub>2</sub> H <sub>2</sub> plasmas studied via quantitative mass spectrometry. Plasma Sources Science and Technology, 2009, 18, 034004.	1.3	16
89	Development of an in situ ellipsometer for deposition and erosion studies at the first wall of a tokamak. Nuclear Fusion, 2009, 49, 045004.	1.6	4
90	Thin film growth from a low pressure plasma excited in a supersonic expanding gas jet. Journal Physics D: Applied Physics, 2009, 42, 095205.	1.3	5

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91	Removal of Model Proteins Using Beams of Argon Ions, Oxygen Atoms and Molecules: Mimicking the Action of Low-Pressure Ar/O <sub>2</sub> ICP Discharges. <i>Plasma Processes and Polymers</i> , 2009, 6, 255-261.	1.6	44
92	Anomalous Roughness Scaling of Well-Ordered Amorphous Fluorocarbon Films Deposited from an Octafluorocyclobutane Plasma. <i>Plasma Processes and Polymers</i> , 2008, 5, 653-660.	1.6	8
93	A robust method to measure metastable and resonant state densities from emission spectra in argon and argon-diluted low pressure plasmas. <i>Journal Physics D: Applied Physics</i> , 2008, 41, 065206.	1.3	74
94	Initial Polymerization Reactions in Particle-Forming Ar/He/C <sub>2</sub> H <sub>2</sub> Plasmas Studied via Quantitative Mass Spectrometry. <i>Journal of Physical Chemistry A</i> , 2008, 112, 11319-11329.	1.1	28
95	Etching of <i>Bacillus atrophaeus</i> by oxygen atoms, molecules and argon ions. <i>Journal of Physics: Conference Series</i> , 2008, 133, 012012.	0.3	12
96	Inactivation of <i>Bacillus atrophaeus</i> and of <i>Aspergillus niger</i> using beams of argon ions, of oxygen molecules and of oxygen atoms. <i>Journal Physics D: Applied Physics</i> , 2008, 41, 115207.	1.3	62
97	Deposition of carbon-free silicon dioxide from pure hexamethyldisiloxane using an atmospheric microplasma jet. <i>Applied Physics Letters</i> , 2008, 92, .	1.5	64
98	Optical and electrical characterization of an atmospheric pressure microplasma jet for Ar•CH <sub>4</sub> and Ar•C <sub>2</sub> H <sub>2</sub> mixtures. <i>Journal of Applied Physics</i> , 2007, 101, 103307.	1.1	91
99	The role of chemical sputtering during plasma sterilization of <i>Bacillus atrophaeus</i> . <i>Journal Physics D: Applied Physics</i> , 2007, 40, 2826-2830.	1.3	59
100	The search for growth precursors in reactive plasmas: from nanoparticles to microplasmas. <i>Plasma Sources Science and Technology</i> , 2007, 16, S94-S100.	1.3	2
101	Heating of a dual frequency capacitively coupled plasma via the plasma series resonance. <i>Plasma Sources Science and Technology</i> , 2007, 16, 839-848.	1.3	80
102	Time-Resolved Molecular Beam Mass Spectrometry of the Initial Stage of Particle Formation in an Ar/He/C <sub>2</sub> H <sub>2</sub> Plasma. <i>Journal of Physical Chemistry A</i> , 2007, 111, 10453-10459.	1.1	49
103	Thin film deposition by means of atmospheric pressure microplasma jet. <i>Plasma Physics and Controlled Fusion</i> , 2007, 49, B419-B427.	0.9	81
104	Rotation of a nanoparticle cloud in an inductively coupled plasma induced by weak static magnetic fields. <i>Plasma Sources Science and Technology</i> , 2007, 16, 774-784.	1.3	11
105	Atmospheric pressure microplasma jet as a depositing tool. <i>Applied Physics Letters</i> , 2006, 89, 251504.	1.5	114
106	BIODECON: Plasma Decontamination in Medical Technology. <i>Plasma Processes and Polymers</i> , 2006, 3, 75-76.	1.6	3
107	Characterization of a rotating nanoparticle cloud in an inductively coupled plasma. <i>Plasma Sources Science and Technology</i> , 2006, 15, 556-563.	1.3	26
108	Controlled particle generation in an inductively coupled plasma. <i>Applied Physics Letters</i> , 2006, 88, 141503.	1.5	16

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109	Roughness evolution during a-C:H film growth in methane plasmas. <i>Journal of Applied Physics</i> , 2006, 100, 053302.	1.1	12
110	Ion-induced surface activation, chemical sputtering, and hydrogen release during plasma-assisted hydrocarbon film growth. <i>Journal of Applied Physics</i> , 2005, 97, 094904.	1.1	47
111	Control of the plasma chemistry of a pulsed inductively coupled methane plasma. <i>Plasma Sources Science and Technology</i> , 2005, 14, 543-548.	1.3	30
112	Growth precursors for a-C:H film deposition in pulsed inductively coupled methane plasmas. <i>Journal of Applied Physics</i> , 2005, 98, 073302.	1.1	46
113	Particle-induced oscillations in inductively coupled plasmas. <i>Plasma Sources Science and Technology</i> , 2004, 13, 285-292.	1.3	7
114	Elementary processes in plasma-surface interaction: H-atom and ion-induced chemisorption of methyl on hydrocarbon film surfaces. <i>Progress in Surface Science</i> , 2004, 76, 21-54.	3.8	73
115	Can plasma experiments unravel microscopic surface processes in thin film growth and erosion? Implications of particle-beam experiments on the understanding of a-C:H growth. <i>Vacuum</i> , 2003, 71, 361-376.	1.6	11
116	Characterisation of deposited hydrocarbon layers below the divertor and in the pumping ducts of ASDEX Upgrade. <i>Journal of Nuclear Materials</i> , 2003, 313-316, 429-433.	1.3	33
117	Consequences of the temperature and flux dependent sticking coefficient of methyl radicals for nuclear fusion experiments. <i>Nuclear Fusion</i> , 2003, 43, 25-29.	1.6	14
118	Chemical sputtering of hydrocarbon films. <i>Journal of Applied Physics</i> , 2003, 94, 2373-2380.	1.1	109
119	The influence of hydrogen ion bombardment on plasma-assisted hydrocarbon film growth. <i>Diamond and Related Materials</i> , 2003, 12, 85-89.	1.8	29
120	Particle-beam experiment to study heterogeneous surface reactions relevant to plasma-assisted thin film growth and etching. <i>Review of Scientific Instruments</i> , 2003, 74, 5123-5136.	0.6	24
121	Direct verification of the ion-neutral synergism during hydrocarbon film growth. <i>Journal of Applied Physics</i> , 2003, 93, 3352-3358.	1.1	31
122	Temperature dependence of the sticking coefficient of methyl radicals at hydrocarbon film surfaces. <i>Journal of Chemical Physics</i> , 2002, 116, 5125.	1.2	35
123	Chemical sputtering of hydrocarbon films by low-energy Ar <sup>+</sup> ion and H atom impact. <i>Nuclear Fusion</i> , 2002, 42, L27-L30.	1.6	58
124	Growth mechanism of amorphous hydrogenated carbon. <i>Diamond and Related Materials</i> , 2002, 11, 969-975.	1.8	112
125	Advantages of the optical cavity substrate for real time infrared spectroscopy of plasma-surface interactions. <i>Journal of Applied Physics</i> , 2002, 91, 4840-4845.	1.1	8
126	Formation of polymer-like hydrocarbon films from radical beams of methyl and atomic hydrogen. <i>Thin Solid Films</i> , 2002, 402, 1-37.	0.8	88



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127	Simultaneous interaction of methyl radicals and atomic hydrogen with amorphous hydrogenated carbon films. <i>Journal of Applied Physics</i> , 2001, 89, 2979-2986.	1.1	65
128	Simultaneous interaction of methyl radicals and atomic hydrogen with amorphous hydrogenated carbon films, as investigated with optical in situ diagnostics. <i>Applied Physics A: Materials Science and Processing</i> , 2001, 72, 551-556.	1.1	28
129	Surface reactions of hydrocarbon radicals: suppression of the re-deposition in fusion experiments via a divertor liner. <i>Journal of Nuclear Materials</i> , 2001, 290-293, 231-237.	1.3	29
130	Quantification of a radical beam source for methyl radicals. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2001, 19, 101-107.	0.9	37
131	Hydrogen elimination as a key step for the formation of polymerlike hydrocarbon films. <i>Journal of Applied Physics</i> , 2001, 90, 3585-3594.	1.1	35
132	Infrared analysis of thin films: amorphous, hydrogenated carbon on silicon. <i>Brazilian Journal of Physics</i> , 2000, 30, 508-516.	0.7	16
133	Surface processes during thin-film growth. <i>Plasma Sources Science and Technology</i> , 2000, 9, 455-467.	1.3	72
134	Direct identification of the synergism between methyl radicals and atomic hydrogen during growth of amorphous hydrogenated carbon films. <i>Applied Physics Letters</i> , 2000, 76, 676-678.	1.5	77
135	Novel method for absolute quantification of the flux and angular distribution of a radical source for atomic hydrogen. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2000, 18, 995-1001.	0.9	63
136	Surface loss probabilities of hydrocarbon radicals on amorphous hydrogenated carbon film surfaces. <i>Journal of Applied Physics</i> , 2000, 87, 2719-2725.	1.1	89
137	Thermal conductivity of amorphous carbon thin films. <i>Journal of Applied Physics</i> , 2000, 88, 6317-6320.	1.1	158
138	Surface loss probabilities of hydrocarbon radicals on amorphous hydrogenated carbon film surfaces: Consequences for the formation of re-deposited layers in fusion experiments. <i>Nuclear Fusion</i> , 1999, 39, 1451-1462.	1.6	99
139	Direct insertion of SiH <sub>3</sub> radicals into strained Si-Si surface bonds during plasma deposition of hydrogenated amorphous silicon films. <i>Physical Review B</i> , 1999, 59, 5791-5798.	1.1	54
140	Surface loss probabilities of the dominant neutral precursors for film growth in methane and acetylene discharges. <i>Applied Physics Letters</i> , 1999, 74, 3800-3802.	1.5	52
141	Erosion of thin hydrogenated carbon films in oxygen, oxygen/hydrogen and water plasmas. <i>Journal of Nuclear Materials</i> , 1999, 264, 48-55.	1.3	60
142	Plasma chemical vapor deposition of hydrocarbon films: The influence of hydrocarbon source gas on the film properties. <i>Journal of Applied Physics</i> , 1999, 86, 3988-3996.	1.1	221
143	Structure of plasma-deposited amorphous hydrogenated boron-carbon thin films. <i>Thin Solid Films</i> , 1998, 312, 147-155.	0.8	32
144	The interaction of atomic hydrogen with very thin amorphous hydrogenated silicon films analyzed using in situ real time infrared spectroscopy: Reaction rates and the formation of hydrogen platelets. <i>Journal of Applied Physics</i> , 1998, 84, 489-495.	1.1	59

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145	Surface relaxation during plasma-enhanced chemical vapor deposition of hydrocarbon films, investigated by in situ ellipsometry. Journal of Applied Physics, 1997, 81, 1531-1535.	1.1	51
146	Evidence for atomic H insertion into strained Si-Si bonds in the amorphous hydrogenated silicon subsurface from in situ infrared spectroscopy. Applied Physics Letters, 1997, 71, 3832-3834.	1.5	29
147	Interaction of hydrogen plasmas with hydrocarbon films, investigated by infrared spectroscopy using an optical cavity substrate. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1997, 15, 402-407.	0.9	27
148	Surface relaxation during plasma chemical vapor deposition of diamond-like carbon films, investigated by in-situ ellipsometry. Thin Solid Films, 1997, 308-309, 195-198.	0.8	3
149	Surface reactions during plasma-enhanced chemical vapor deposition of hydrocarbon films. Nuclear Instruments & Methods in Physics Research B, 1997, 125, 323-327.	0.6	6
150	Multivariate analysis of noise-corrupted PECVD data. Thin Solid Films, 1997, 307, 65-70.	0.8	3
151	Secondary electron emission coefficient of C:H and Si:C thin films and some relations to their morphology and composition. Diamond and Related Materials, 1996, 5, 1087-1095.	1.8	3
152	Growth and erosion of hydrocarbon films investigated by in situ ellipsometry. Journal of Applied Physics, 1996, 79, 1092.	1.1	129
153	Erosion of amorphous hydrogenated boron-carbon thin films. Journal of Nuclear Materials, 1996, 231, 151-154.	1.3	11
154	The Role of Ions for the Deposition of Hydrocarbon Films, investigated by In-Situ Ellipsometry. Materials Research Society Symposia Proceedings, 1995, 388, 355.	0.1	5
155	A novel setup for spectroscopic ellipsometry using an acousto-optic tuneable filter. Review of Scientific Instruments, 1995, 66, 3545-3550.	0.6	14
156	Mechanisms of the Deposition of Hydrogenated Carbon Films. Japanese Journal of Applied Physics, 1995, 34, 2163-2171.	0.8	53
157	Role of hydrogen ions in plasma-enhanced chemical vapor deposition of hydrocarbon films, investigated by in situ ellipsometry. Applied Physics Letters, 1995, 66, 1322-1324.	1.5	38
158	A combined plasma-surface model for the deposition of C:H films from a methane plasma. Journal of Applied Physics, 1994, 75, 7718-7727.	1.1	110
159	Deposition of dense C:H films at elevated substrate temperature. Diamond and Related Materials, 1993, 2, 251-254.	1.8	6
160	Deposition of dense hydrocarbon films from a nonbiased microwave plasma. Applied Physics Letters, 1993, 62, 937-939.	1.5	62
161	Synchronising optical emission spectroscopy to spokes in magnetron sputtering discharges. Plasma Sources Science and Technology, 0, , .	1.3	7